

**METHOD AND APPARATUS FOR ADJUSTING THE THICKNESS OF A
LAYER OF SEMICONDUCTOR MATERIAL**

ABSTRACT

5 A method for adjusting the thickness of a thin semiconductor material layer. The technique includes measuring the layer to establish a thickness profile, comparing the measured thickness profile with stored standard profiles, wherein each standard profile is
10 stored in association with respective thickness adjustment specifications, selecting a stored standard profile to associate the layer with the respective thickness adjustment specification, and adjusting the thickness of the layer in accordance with the thickness
15 adjustment specification. The invention also provides apparatus for adjusting the thickness of a thin semiconductor material layer.